

# Surface sulfurization study on the CIGSe thin-film solar cell

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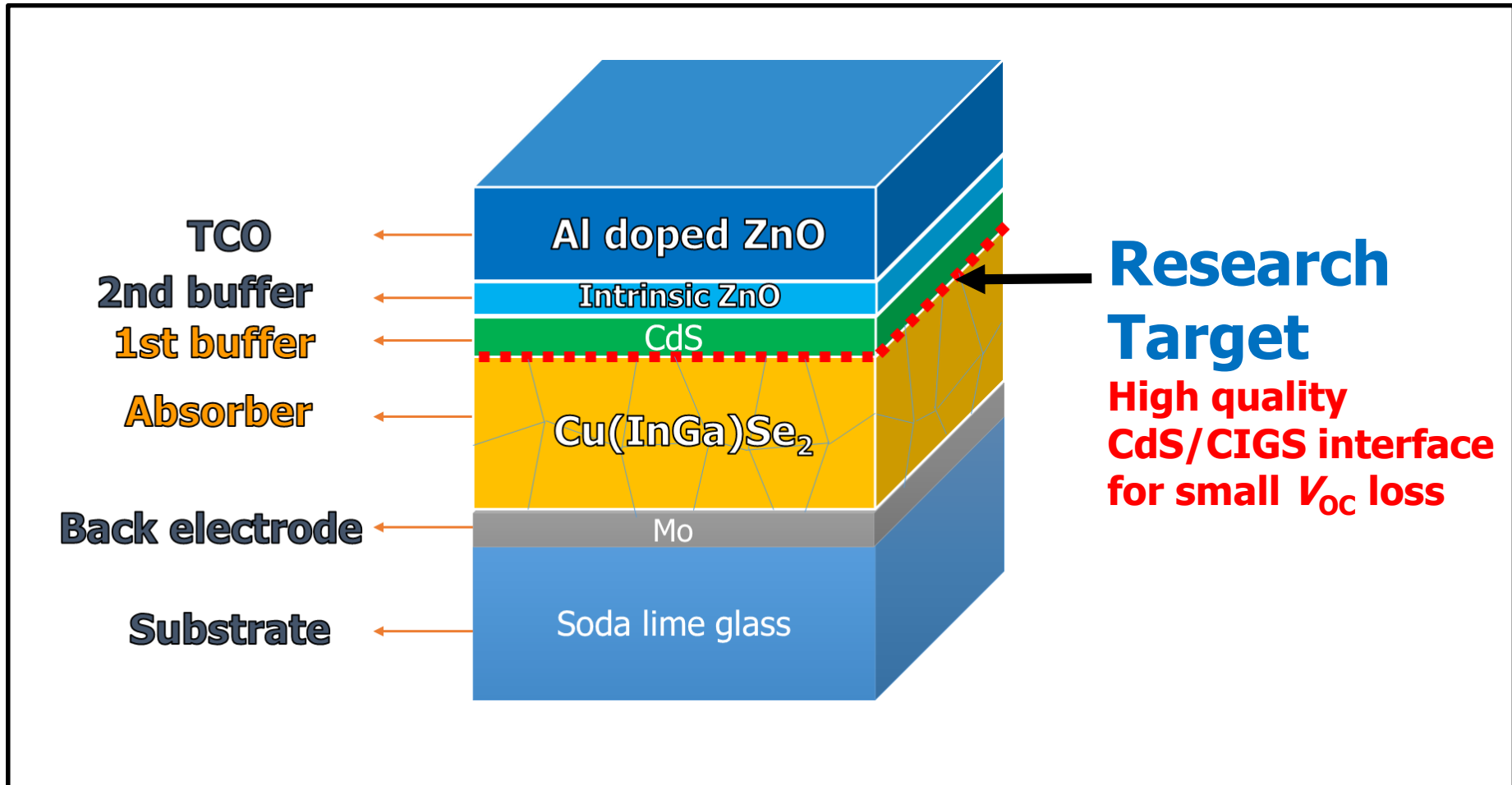
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Environment

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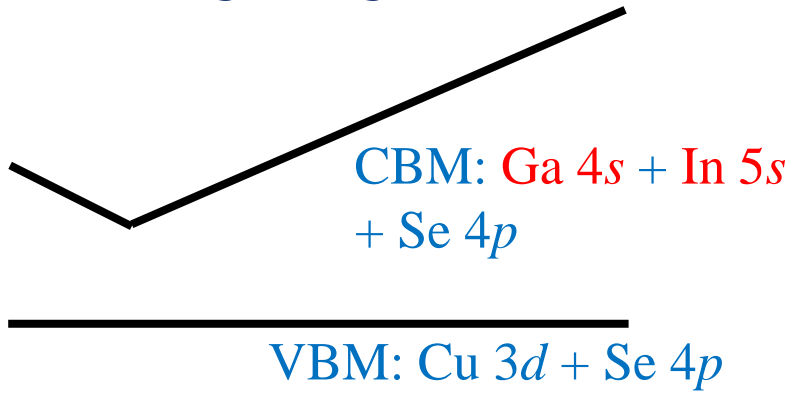
- Introduction – Surface sulfurization
- Experimental method
- Results and discussion
  - Thin-film analysis – **Forming of front-graded bandgap by sulfurization**
  - Device analysis – **Reduced recombination**
- Summary

# Structure of CIGSe/Research Target

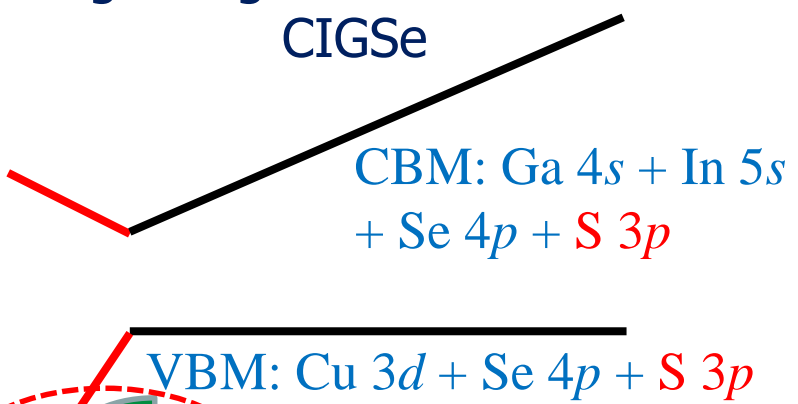


# Surface sulfurization

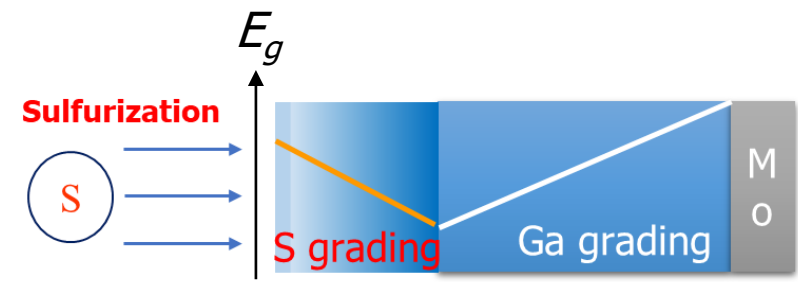
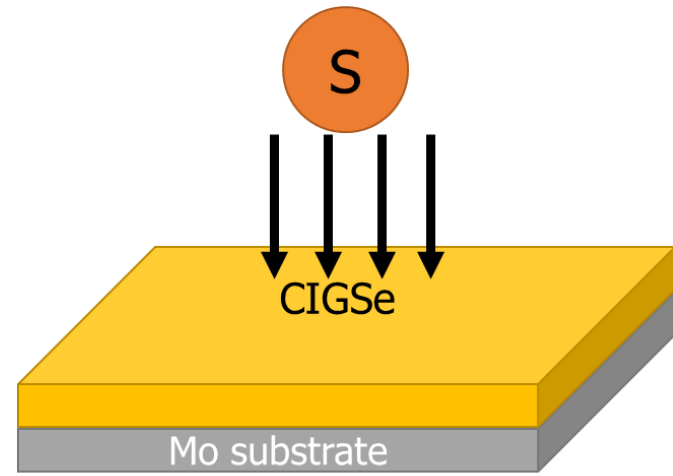
Band grading of CIGSe



Band grading of **surface sulfurized** CIGSe

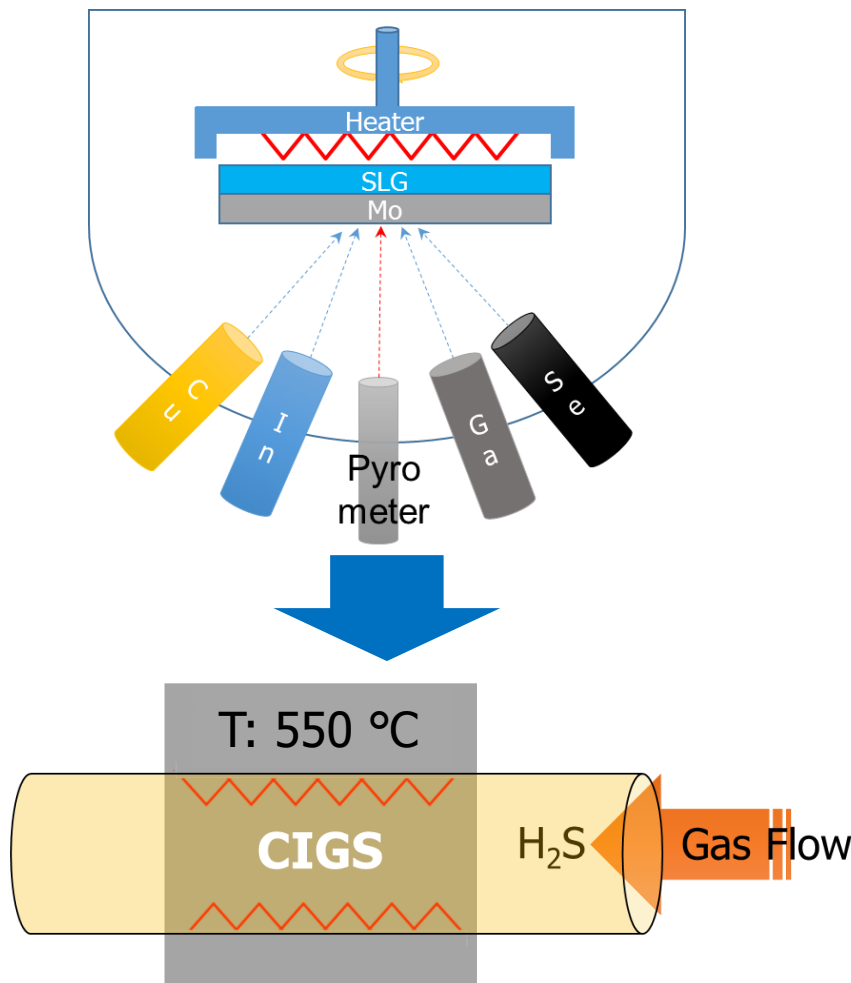


hole-blocking barrier  
→ **Reduced interface recombination**



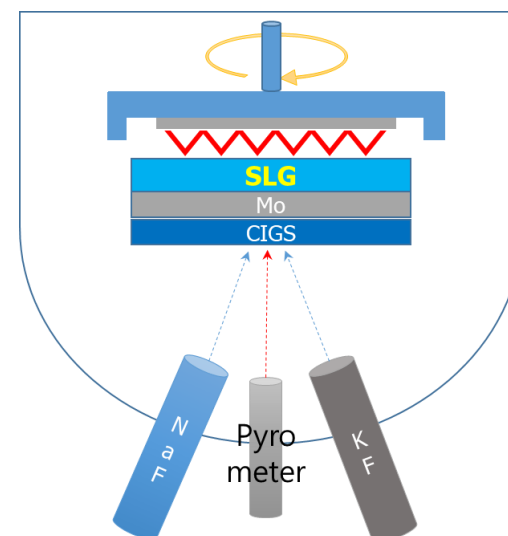
- Forming single graded bandgap CIGSe
- Forming front bandgap grading by incorporation of S

# Experimental Method



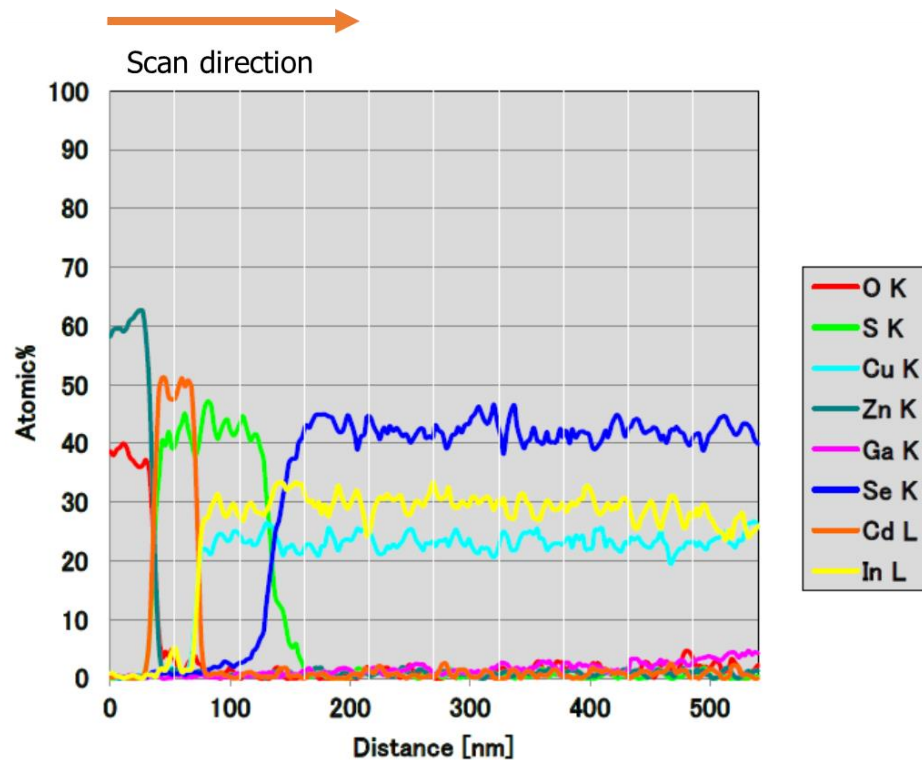
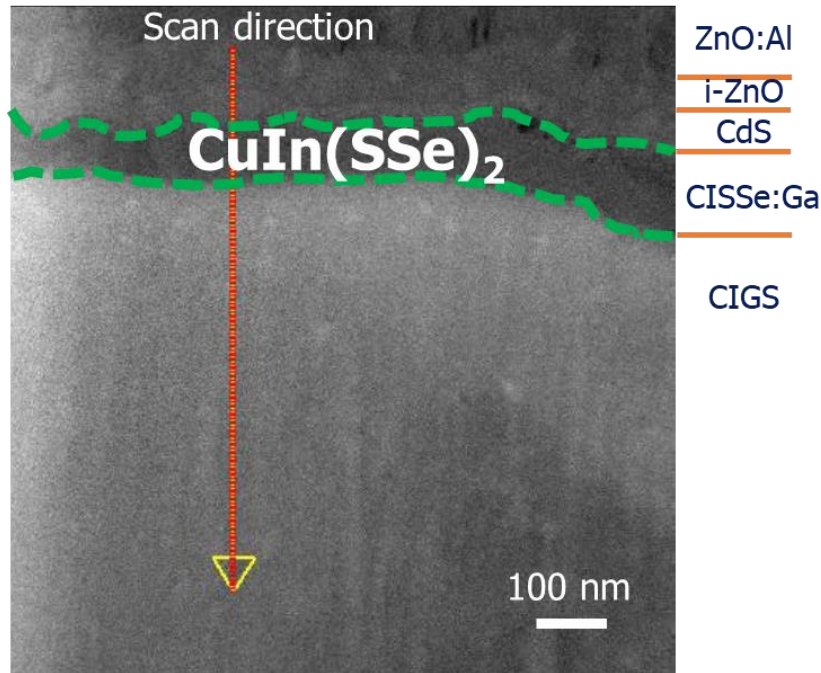
**Annealing pressure:  $5 \sim 8 \times 10^4$  Pa**

- Single graded CIGSe was grown by using MBE
- Ga was not incorporated at 3rd stage.
- Surface sulfurization in the annealing furnace
- Alkali-PDT using MBE chamber



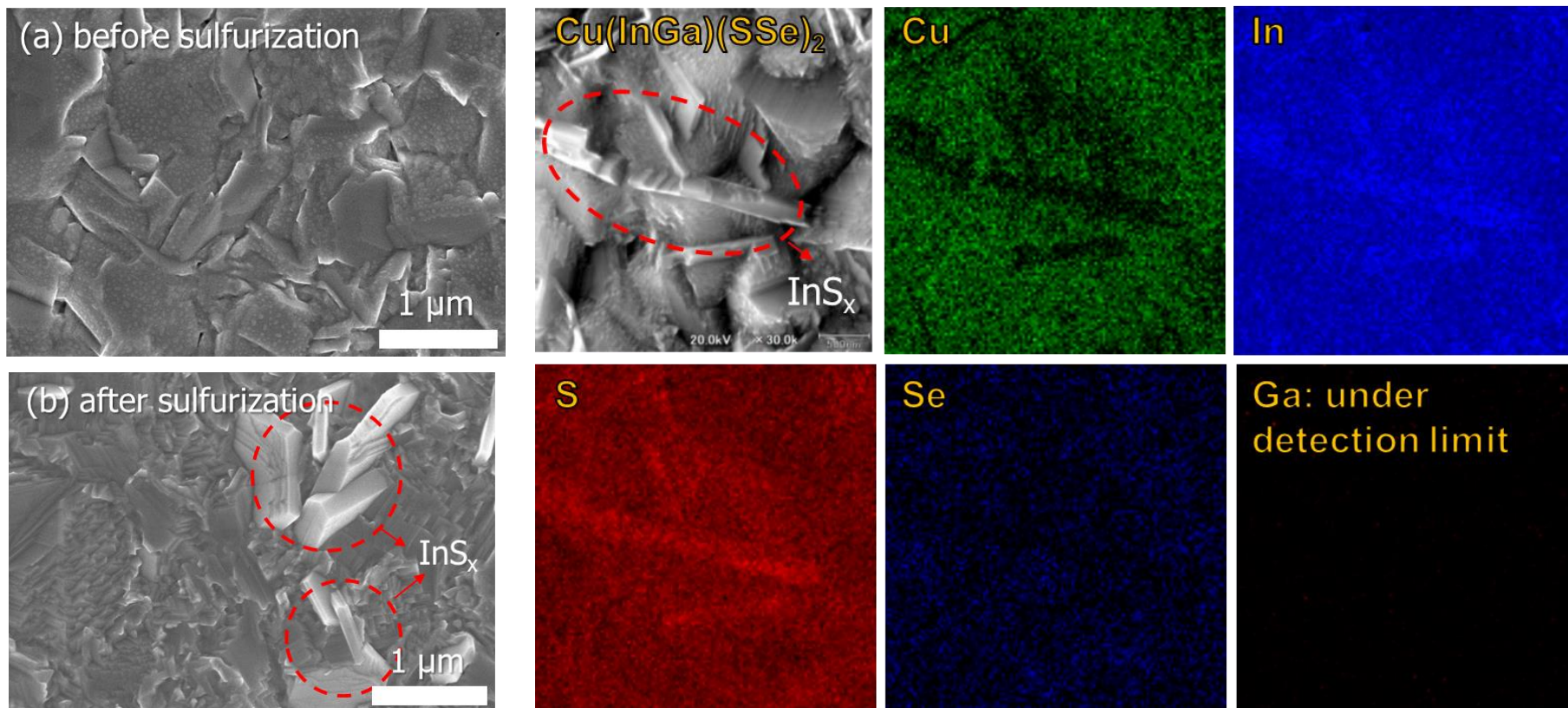
# Depth profile of surface sulfurized CIGSe

## TEM-EDS analysis



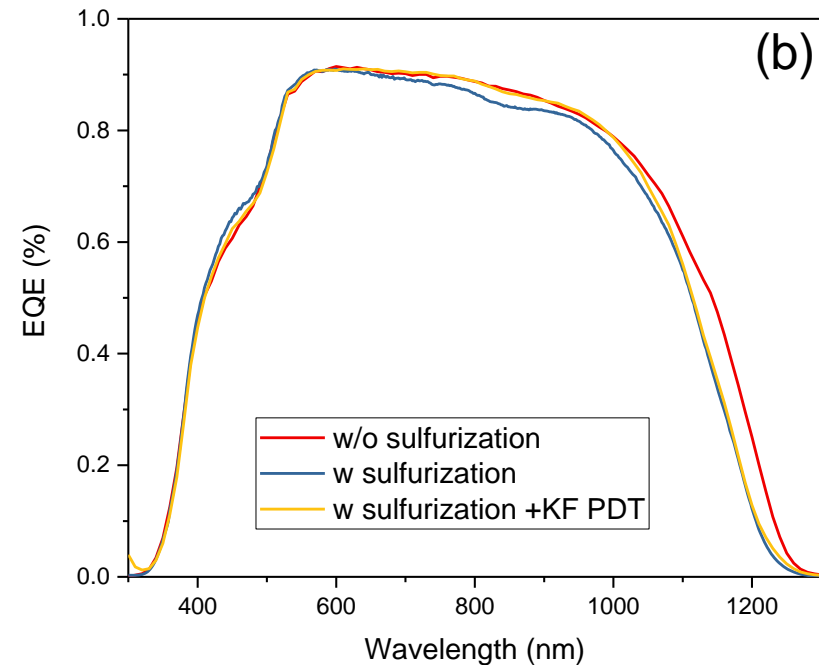
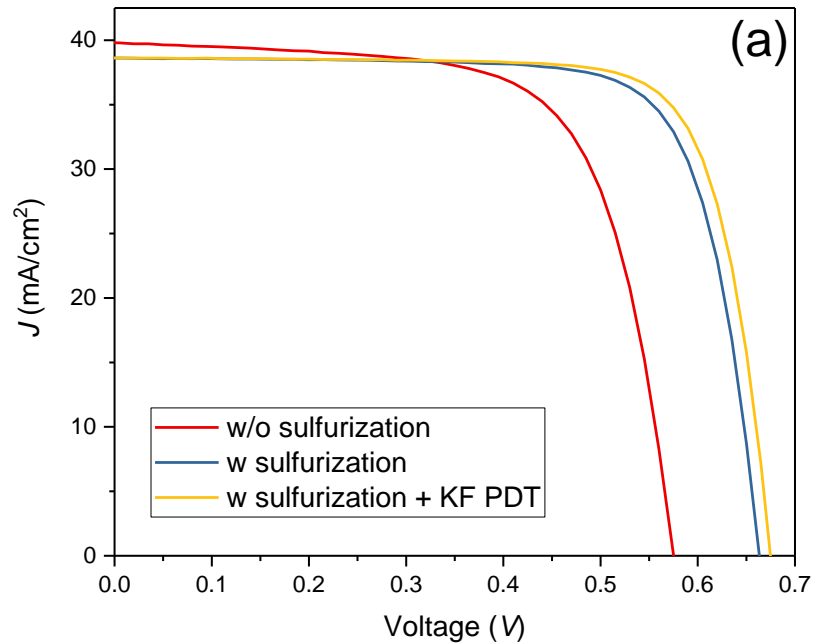
- ✓ Graded S contents cause front-graded bandgap.
- ✓ Ga intensity was very low in the near interface region.
- ✓ After sulfurization Ga doped CISSe (CISSe:Ga) was formed on the CIGSe layer.

# Surface morphology (SEM) and surface elemental mapping images (measured by AES)



- ✓ After sulfurization Ga was not detected at the surface sulfurized CIGSe.
- ✓ Very thin CISSe was formed.
- ✓  $\text{InS}_x$  secondary phase was observed. → **no harmful effects on the devices**

# J-V and EQE analysis

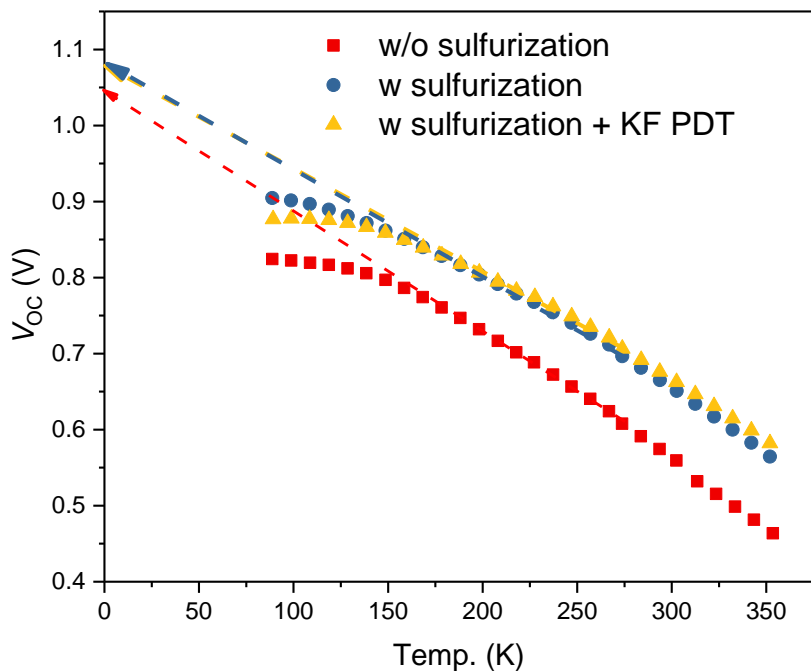


Sample	Eff. (%)	$V_{OC}$ (V)	$J_{SC}$ (mA/cm <sup>2</sup> )	FF	$R_{SH}$ (k $\Omega$ ·cm <sup>2</sup> )	$R_S$ ( $\Omega$ ·cm <sup>2</sup> )	$A$	$J_0$ (mA/cm <sup>2</sup> )	$E_g$ (eV)	$E_g/q - V_{OC}$ (V)
w/o S	15.5	0.58	39.8	0.68	0.33	0.32	1.92	3.6.E-04	1.07	0.49
w S	19.4	0.66	38.6	0.76	3.13	0.37	1.48	1.0.E-06	1.09	0.43
w S +KF PDT	20.1	0.68	38.6	0.77	3.03	0.37	1.40	3.1.E-07	1.09	0.41



# Reduced interface recombination

Activation energy ( $E_a$ ) measured by temp. dependence of  $J-V$  analysis



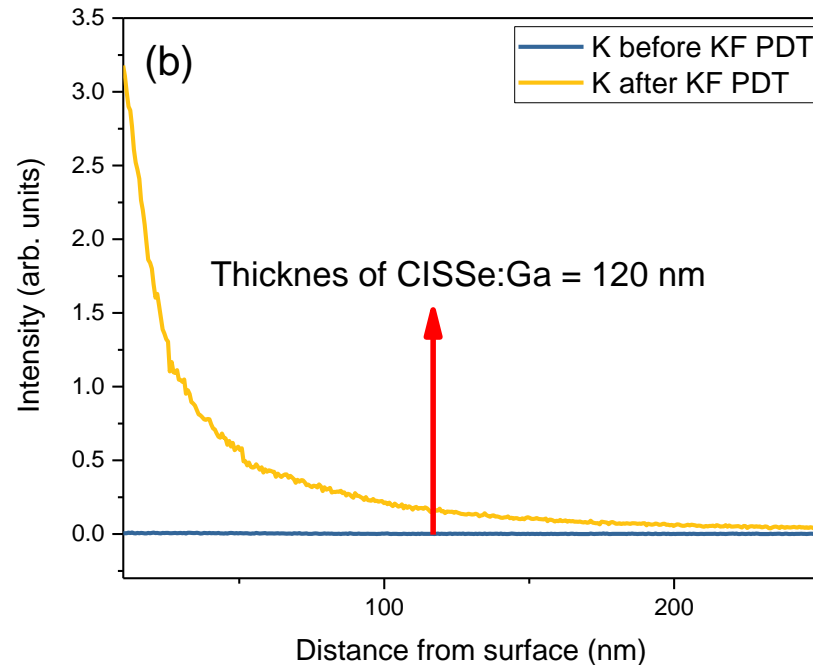
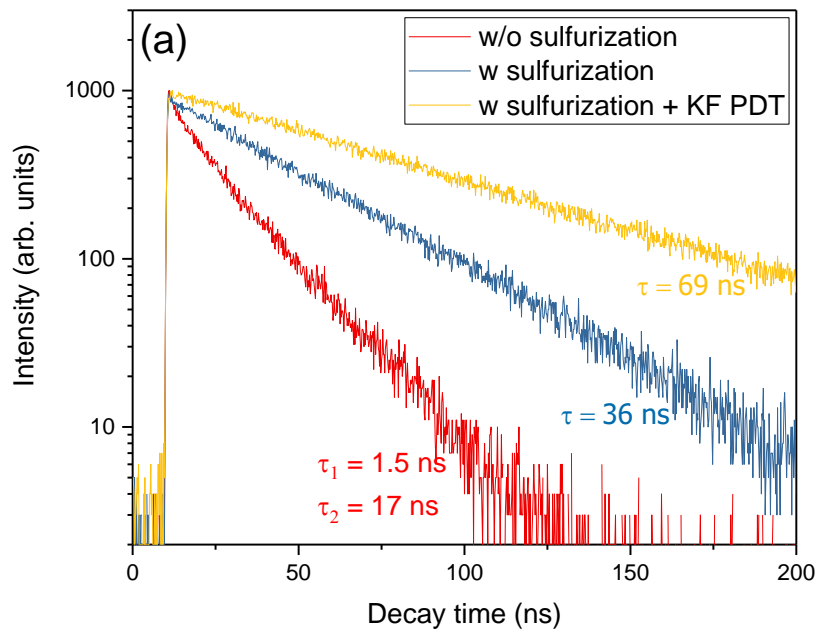
- $E_g > E_a$   
→ Large interface recombination
- The CIGSe with surface sulfurized exhibits almost same  $E_a$ .

Sample	$E_g$ (eV)	$E_a$ (eV)
w/o S	1.07	1.04
w S	1.09	1.08
w S +KF PDT	1.09	1.08

- ✓ Newly formed CIGSe:Ga layer was effective in reducing interface recombination → Front graded bandgap and hole blocking layer
- ✓ What is the role of KF-PDT?

# The role of KF-PDT

## Carrier lifetime measurement (TRPL) and depth profile of CIGSe with KF PDT (GD-OES)

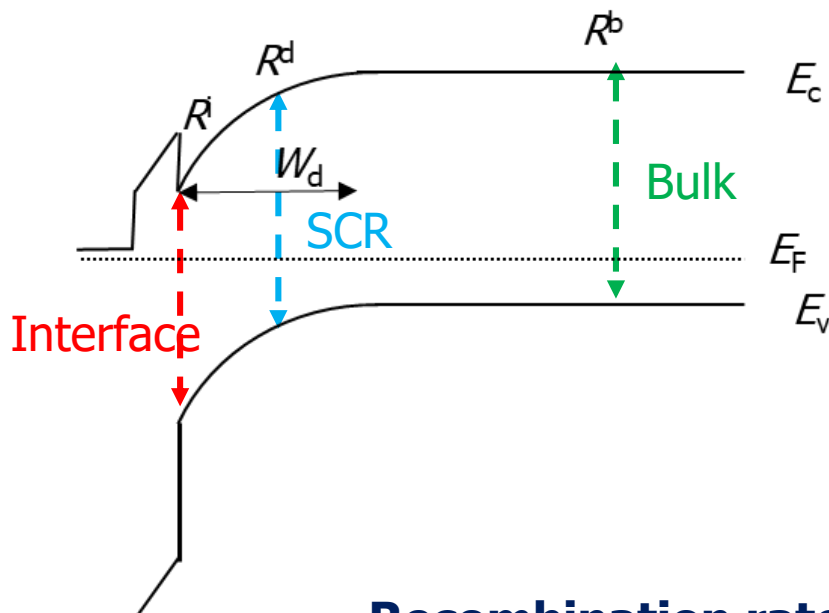


$$I(t) = I_1(0)\exp\left(-\frac{t}{\tau_1}\right) + I_2(0)\exp\left(-\frac{t}{\tau_2}\right),$$

- The KF-PDT device shows improved carrier lifetime in bulk.
- K penetrated bulk region of CIGSe.
- **Defect passivation, grain boundaries passivation, etc.**

# Reduction of recombination

Band diagram of CIGSe absorber



$$V_{OC} = \frac{2kT}{q} \ln \left[ \frac{1}{2} \frac{R_0^d}{R_0^i + R_0^b} \left( \sqrt{4GW \frac{R_0^i + R_0^b}{(R_0^d)^2} + 1} - 1 \right) \right]$$

$$E_a = \frac{R_0^i q \phi_{b0} + R_0^b E_g}{R_0^i + R_0^b}$$

$$R^i = R_0^i e^{qV/kT}, R^d = R_0^d e^{qV/2kT} \text{ and } R^b = R_0^b e^{qV/kT}$$

J. V. Li, S. Grover, M. A. Contreras, K. Ramanathan, D. Kuciauskas and R. Noufi: Solar Energy Materials and Solar Cells, **124** (2014) 143.

## Recombination rate at $V = V_{OC}$ and $T = 25 \text{ }^\circ\text{C}$

Sample	Interface, $R^i$ ( $\text{cm}^{-2} \cdot \text{s}^{-1}$ )	SCR, $R^d$ ( $\text{cm}^{-2} \cdot \text{s}^{-1}$ )	Bulk, $R^b$ ( $\text{cm}^{-2} \cdot \text{s}^{-1}$ )
w/o sulfurization	$1.7 \times 10^{17}$	$6.7 \times 10^{17}$	$2.5 \times 10^{18}$
w sulfurization	$3.6 \times 10^{15}$	$2.6 \times 10^{16}$	$1.5 \times 10^{17}$
<b>with sulfurization +KF-PDT</b>	$3.2 \times 10^{15}$	$2.1 \times 10^{16}$	<b><math>9.9 \times 10^{16}</math></b>

# Summary

- ✓ Demonstrated **surface sulfurization effect** on the CIGSe.
  - ✓ Newly formed **CISSe:Ga** layer was effective in reduction of recombination at buffer/CIGSe interface.
  - ✓ Reduction of  $V_{OC}$  loss
- ✓ Demonstrated **reduction of recombination in bulk** by **KF-PDT** on the surface sulfurized CIGSe.
  - ✓ Achieved high efficiency of 20.1%
  - ✓ Achieved small  $V_{OC}$  deficit of 0.41 V

